



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/615,051
Filing Date July 7, 2003
Inventorship Brian A. Vaartstra
Assignee Micron Technology, Inc.
Group Art Unit 2823
Examiner Brook Kebede
Attorney's Docket No. MI22-2308
Customer No. 021567
Title: Methods of Forming a Phosphorus Doped Silicon Dioxide Comprising Layer

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT


References -- See Attached Form PTO-1449

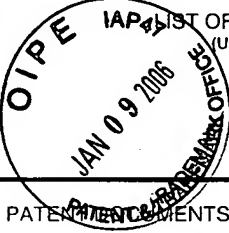
This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to ensure consideration of the references listed on the attached form PTO-1449.

The attached Form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to FEDERAL REGISTER, Vol. 69, No. 182, pg. 56542 (September 21, 2004), no copies of any cited U.S. patents or U.S. published applications are included herewith. Copies of all other cited art are attached. No admission is made regarding whether the listed references are prior art.

Respectfully submitted,

Dated: 1-9-06

By: 
Mark S. Matkin
Reg. No. 32,268

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2308		SERIAL NO. 10/615,051	
 <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT: Brian A. Vaarstra			
				FILING DATE July 7, 2003		GROUP 2823	
U.S. PATENT REFERENCES							
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	2005/0009368	01/05	Vaarstra			
	AB	2005/0112282	05/05	Gordon et al.			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AJ						
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM						
	AN						
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EXAMINER		DATE CONSIDERED					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							